# TABLE OF CONTENTS

**TUESDAY FEBRUARY 27, 2001**

"**CONTINUOUS ELECTRODEIONIZATION PROCESSES FOR PRODUCTION OF ULTRAPURE WATER**"........1  
Li-Shiang Liang, U.S. Filter  
Lu Wang, U.S. Filter

"**CONTROLLING BORON LEVELS IN SEMICONDUCTOR UPW USING AN EXPERIMENTAL ON-LINE BORON ANALYZER**".................................................................15  
Rock Wickham, Integrated Device Technology (IDT)  
Richard Godec, Ionics Instrument Business Group

"**ALTERNATIVE LOW EXTRACTABLE PIPING MATERIALS FOR UPW APPLICATIONS**"..........................34  
Saleem Shakir, PolyOne Corporation  
Jim Isner, Polymer Diagnostics Incorporated  
Bill Weaver, Harvel Plastics, Inc.

"**NOVEL OZONE INJECTION SYSTEM FOR ULTRAPURE WATER**".................................................45  
Tracy Boswell, SEMATECH  
Demas Caravageli, SEMATECH  
Steven J. Hardwick, W.L. Gore & Associates, Inc.

"**SIZING OF PRIMARY UV TOC REDUCERS IN TYPICAL UPW PLANTS: A CLASSICAL APPROACH**".....63  
Avijit Dey, Chemitreat Private Limited  
Gareth Thomas, Chemitreat Private Limited  
Kiran Arun Kekre, Environmental Technology Institute  
Tao GuiHe, Environmental Technology Institute

"**LIQUID CHROMATOGRAPHY – ORGANIC CARBON DETECTION (LC-OCD): A NOVEL DIAGNOSTIC TOOL FOR THE LOCALIZATION OF TOC SOURCES IN UPW PRODUCTION**"..........................83  
Stefan A. Huber, DOC-LABOR

"**A FAST RESPONSE TOC INSTRUMENT FOR SEMICONDUCTOR RECYCLE APPLICATIONS**".............99  
ZiYi Wang, Anatel Corporation  
John Stillian, Anatel Corporation  
Jay Rasmussen, Anatel Corporation

"**DESIGNS AND APPROACHES OF THE ULTRA PURE WATER SYSTEM IN SSMC**".............................111  
Paul Tan, SSMC

"**RECYCLING ULTRAPURE WATER**"..........................................................120  
Lisa Farmen, Texas Instruments
# Table of Contents

**Wednesday February 28, 2001**

"**CMP Waste Water Reclaim**".................................129  
Malek Salamor, Christ AG  
René R. Sauer, Christ AG

"**Chemistry and Treatment of CMP Wastewater**".................................140  
Josh H. Golden, Microbar Incorporated  
Eric Carrubba, Microbar Incorporated  
Robert Small, EKC Technology, Inc.  
Louis Pagan, EKC Technology, Inc.  
Cass Shang, EKC Technology, Inc.  
Srini Ragavan, Dept. of Materials Science and Engineering, University of Arizona

"**Perturbation Detection Analysis: A Method for Comparing Instruments that Measure CMP Slurry Health**".................................153  
Mark R. Litchy, CT Associates, Inc.  
Kristi Nicholes, BOC Edwards, Chemical Management Division  
Donald C. Grant, CT Associates, Inc.  
Rakesh K. Singh, BOC Edwards, Chemical Management Division

"**Evaluation of Measurement Instrumentation and Large Particle Reduction Filtration in CMP Slurry Filter Applications**".................................172  
Holly Linkowich, Filterite Electronics  
Thomas Gutowski, Filterite Electronics  
Anthony Shucosky, Filterite Electronics  
Mark Schmidt, Filterite Electronics

"**Analytical Method Validation in the Semiconductor Industry Applied to High Purity Hydrogen Peroxide**".................................190  
Jean-Marie Collard, Solvay Interox, Inc.  
Yoko Kishi, PerkinElmer Instruments  
Chuck Costanza, Dionex Corporation

"**Testing Components Used in Semiconductor Liquid-Handling Systems to Assure Product Purity and Reliability**".................................214  
Donald C. Grant, CT Associates  
Dennis Chilcote, CT Associates  
Wayne Kelly, CT Associates  
Mark Litchy, CT Associates  
Allen Rodemeyer, Saint-Gobain Performance Plastics  
Dave Henderson, Saint-Gobain Performance Plastics  
Kenji Kingsford, Saint-Gobain Performance Plastics
TABLE OF CONTENTS

THURSDAY MARCH 1, 2001

"THERMODYNAMIC STUDIES OF AQUEOUS SOLUTIONS" .............................................................. 287
SHENG-BAI ZHU, ASYST TECHNOLOGIES, INC.

"THE EFFECT OF DI WATER PARAMETERS ON POST METAL ETCH RESIDUE REMOVAL USING SEMI-AQUEOUS FLUORIDE CLEANING CHEMISTRIES" ......................................................... 299
ROBERT SMALL, EKC TECHNOLOGY, INC.
SIMON J. KIRK, EKC TECHNOLOGY, INC.
MIHAELA CERNAT, EKC TECHNOLOGY, INC.

"ION CHROMATOGRAPHIC DETERMINATION OF IONIC SPECIES ON SILICON WAFER FOLLOWING SURFACE EXTRACTION" ......................................................................................... 311
KANA MOMOJI, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
KIKUO TAKEDA, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
REIKO IIKAWA, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
NORIKO OHKAWA, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
MAKOTO IMAI, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
Taketoshi Fujimoto, SUMIKA CHEMICAL ANALYSIS SERVICE LTD.
Taketoshi Nakahara, Osaka Prefecture University

"PARTICLE REMOVAL EFFECT & MECHANISM OF HYDROGENATED ULPTRAPURE WATER WITH MEGASONIC IRRADIATION" .................................................................................. 323
JUN-ICHI IDA, KURITA WATER INDUSTRIES LTD.
HIROSHI MORITA, KURITA WATER INDUSTRIES LTD.
OSAMU OTA, KURITA WATER INDUSTRIES LTD.
KAZUMI TSUKAMOTO, KURITA WATER INDUSTRIES LTD.
TADAIRO OHMI, NEW INDUSTRY CREATION HATCHERY CENTER (NICHE)

"EFFECT OF SURFACTANTS ON SUB-MICRON PARTICLE REMOVAL DURING WET CHEMICAL CLEANING" .................................................................................................................. 336
SATHEESH KUPPURAO, APPLIED MATERIALS
CHRISTOPHER BEAUDRY, APPLIED MATERIALS
STEVEN VERHAVERBEKE, APPLIED MATERIALS

"INVESTIGATION OF CHELATING AGENTS IN SC-1 SOLUTIONS" ...................................................... 345
CHRISTOPHER BEAUDRY, APPLIED MATERIALS
SATHEESH KUPPURAO, APPLIED MATERIALS
STEVEN VERHAVERBEKE, APPLIED MATERIALS

"THE INTERACTION OF METALLIC CONTAMINANTS FROM LIQUIDS AND SOLID SURFACES" ........ 353
STEVEN VERHAVERBEKE, APPLIED MATERIALS
"How Low Can the Detection Limit Go with VPD-TXRF?"

J. Wang, Balazs Analytical Laboratory
M. Balazs, Balazs Analytical Laboratory
P. Pianetta, Stanford Synchrotron Radiation Laboratory (SSRL)
K. Baur, Stanford Synchrotron Radiation Laboratory (SSRL)
S. Brennan, Stanford Synchrotron Radiation Laboratory (SSRL)